

FOREWORD

Advanced Plasma Science and Its Applications for Nitride and Nanomaterials

To cite this article: 2017 *Jpn. J. Appl. Phys.* **56** 01A001

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Advanced Plasma Science and Its Applications for Nitride and Nanomaterials

This special issue consists of peer-reviewed papers based on presentations at the 8th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials (ISPlasma2016) held at Nagoya University, Nagoya, Japan during March 6–10, 2016. The ISPlasma2016 Organizing Committee is associated with the project “Tokai Region Nano-technology Manufacturing Cluster,” implemented by MEXT (Ministry of Education, Culture, Sports, Science and Technology) Knowledge Cluster Initiative. The scope of the symposium is advanced plasma science and technology, including plasma sources, diagnostics, modeling and/or simulation of plasma enhanced processing, and its application for processing and manufacturing of wide-bandgap materials and nanomaterials research, also application for biosensing, plasma biology and medicine.

A total numbers of 361 papers including 48 plenary & invited talks and 313 contributed talks were presented at the symposium, attended by 391 participants including 148 from overseas. This special issue contains 45 papers, including 1 Progress Review, which were submitted based on presentations at the symposium and have met the standard reviewing process of Japanese Journal of Applied Physics. The ISPlasma2016 committee sincerely hopes that this special issue forms a valuable contribution to the knowledge of plasma science and its applications, and stimulates further development of the field.

January 2017

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